	L#	Hits	Search Text	DBs
1	L1	3682	(microlens\$4 or micro adj lens\$4 or lenslet or (lens\$4 near2 array)).ti,ab.	US- PGPUB; USPAT
2	L2	3529	430/321,330.ccls.	US- PGPUB; USPAT
3	L3	91	1 and 2	US- PGPUB; USPAT
4	L4	436763	(heat\$4 or melt\$4 or thermal\$4 or reflow\$4).ti,ab.	US- PGPUB; USPAT
5	L5	163	216/26.ccls.	US- PGPUB; USPAT
6	L6	25	4 and 5	US- PGPUB; USPAT
7	L7	1122	359/619.ccls.	US- PGPUB; USPAT
8	L8	41	4 and 7	US- PGPUB; USPAT
9	L9	38	8 not (3 or 6)	US- PGPUB; USPAT
10	L10	3048	385/14.ccls.	US- PGPUB; USPAT
11	L11	17	1 and 10	US- PGPUB; USPAT
12	L12	2022	385/33,35.ccls.	US- PGPUB; USPAT
13	L13	115	4 and 12	US- PGPUB; USPAT
14	L14	114	13 not (3 or 6 or 8 or 11)	US- PGPUB; USPAT
15	L15	1157	((ball or spher\$6) near3 lens).ti,ab.	US- PGPUB; USPAT

	L#	Hits	Search Text	DBs
16	L16	3	2 and 15	US- PGPUB; USPAT
17	L17	8		US- PGPUB; USPAT
18	L18	312	(1 or 15) and 4	US- PGPUB; USPAT
19	L19	24727	(silica or silicon adj dioxide or sio\$4).ti,ab.	US- PGPUB; USPAT
20	L20	12	18 and 19	US- PGPUB; USPAT
21	L21	7684	("sio.sub.2").ti,ab.	US- PGPUB; USPAT
22	L22	4 .	18 and 21	US- PGPUB; USPAT
23	L23	79663	(photolithograph\$8 or lithograph\$8 or resist or photoresist or photosensitiv\$8 or photopolymer\$8 or (photo or light or uv or ultraviolet or radait\$6 or irradiat\$6) near3 (sensitiv\$8 or polymer or polymeriz\$8 or polymeris\$8)).ti,ab.	US- PGPUB; USPAT
24	L24	50437	etch\$4.ti,ab.	US- PGPUB; USPAT
25	L25	28	18 and 23 and 24	US- PGPUB; USPAT
26	L26	67589	clad\$4	US- PGPUB; USPAT
27	L27	1997316	(heat\$4 or melt\$4 or thermal\$4 or reflow\$4)	US- PGPUB; USPAT
28	L28	25991	(microlens\$4 or micro adj lens\$4 or lenslet or (lens\$4 near2 array))	US- PGPUB; USPAT
29	L29	19429	((ball or spher\$6) near3 lens)	US- PGPUB; USPAT

	L#	Hits	Search Text	DBs
30	L30	83	26 same 27 same (28 or 29)	US- PGPUB; USPAT
31	L31	567246	(silica or silicon adj dioxide or sio\$4 or "sio.sub.2")	US- PGPUB; USPAT
32	L32	210392	dope\$4 or doping	US- PGPUB; USPAT
33	L33	21364	31 with 32	US- PGPUB; USPAT
34	L34	11	27 same (28 or 29) same 33	US- PGPUB; USPAT
35	L35	264	cho-jae\$.in.	US- PGPUB; USPAT
36	L36	427	jung-sun\$.in.	US- PGPUB; USPAT
37	L37	3	(1 or 15) and (35 or 36)	US- PGPUB; USPAT
38	L38	17017	(microlens\$4 or micro adj lens\$4 or lenslet or (lens\$4 near2 array))	EPO; JPO; DERWE NT; IBM_TDB
39	L39	7083	((ball or spher\$6) near3 lens)	EPO; JPO; DERWE NT; IBM_TDB
40	L40	3318605	(heat\$4 or melt\$4 or thermal\$4 or reflow\$4)	EPO; JPO; DERWE NT; IBM_TDB

	L#	Hits	Search Text	DBs
41	L41	95040	clad\$4	EPO; JPO; DERWE NT; IBM_TDB
42	L42	37	(38 or 39) and 40 and 41	EPO; JPO; DERWE NT; IBM_TDB
43	L43	291329	(silica or silicon adj dioxide or sio\$4 or "sio.sub.2")	EPO; JPO; DERWE NT; IBM_TDB
44	L44	96971	dope\$ or doping	EPO; JPO; DERWE NT; IBM_TDB
45	L45	4266	43 with 44	EPO; JPO; DERWE NT; IBM_TDB
46	L46	4	(38 or 39) and 40 and 45	EPO; JPO; DERWE NT; IBM_TDB
47	L47	500569	(photolithograph\$8 or lithograph\$8 or resist or photoresist or photosensitiv\$8 or photopolymer\$8 or (photo or light or uv or ultraviolet or radait\$6 or irradiat\$6) near3 (sensitiv\$8 or polymer or polymeriz\$8 or polymeris\$8))	EPO; JPO; DERWE NT; IBM_TDB

	L#	Hits	Search Text	DBs
48	L48	273729	etch\$4	EPO; JPO; DERWE NT; IBM_TDB
49	L49	163	(38 or 39) and 40 and 47 and 48	EPO; JPO; DERWE NT; IBM_TDB